






ERRATUM | AUGUST 24 2020

Erratum: Power Matching to Pulsed Inductively Coupled Plasmas [J. Appl. Phys. 127, 133302 (2020)] **FREE**

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This erratum applies to the paper “Power Matching to Pulsed Inductively Coupled Plasmas.”¹ In this paper, we discussed power deposition in continuous wave and pulsed electronegative Ar/Cl₂ inductively coupled plasmas considering E-H (capacitive-to-inductive) transitions and optimization of power transfer using an impedance matching network (IMN). There were typographical errors regarding the power reflection coefficient Γ described in the *Introduction*. The reflection coefficient Γ_R in Eq. (1) of Ref. 1,

$$\Gamma_R = \frac{Z_L - Z_0}{Z_L + Z_0}, \quad (1)$$

is the *electric field reflection coefficient* and not the power reflection coefficient as cited in the paper. The power reflection coefficient Γ

comes from the magnitude of Γ_R ,

$$\Gamma = |\Gamma_R|^2. \quad (2)$$

This coefficient is used later in the paper to characterize the matching efficiency. Therefore, in Eq. (8) of Ref. 1, Γ should be

$$\Gamma = \left| \frac{Z_M - Z_0}{Z_M + Z_0} \right|^2, \quad (3)$$

where Z_M is the input impedance to the IMN. Correcting these typographical errors has no impact on the results or the conclusions presented in the paper.

REFERENCES

¹C. Qu, S. J. Lanham, S. C. Shannon, S. K. Nam, and M. J. Kushner, *J. Appl. Phys.* 127, 133302 (2020).